





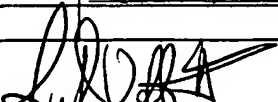


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|--|--|---------------------------------------|
| Form 1449 (Modified) Information Disclosure Statement By Applicant (Use Several Sheets if Necessary) | Atty Docket No. KLA1P119 | Application No.: 10/760,149 |
| | Applicant: Mieher et al. | |
| | Filing Date January 17, 2004 | Group 2877 |
| | | |

U.S. Patent Documents

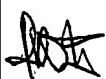

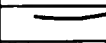

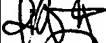

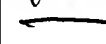
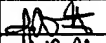
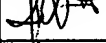




| Examiner Initial | No. | Patent No. | Date | Patentee | Class | Sub- class | Filing Date |
|---|-----|--------------|----------|-------------------|-------|---------------|----------------|
|  ↓  | A1 | 4,908,656 | 03/13/90 | Suwa et al. | | | 01/19/89 |
| | A2 | 5,607,800 | 03/04/97 | Ziger | | | 02/15/95 |
| | A3 | 5,629,772 | 05/13/97 | Ausschnitt | | | 12/20/94 |
| | A4 | 5,790,254 | 08/04/98 | Ausschnitt | | | 06/26/96 |
| | A5 | 5,902,703 | 05/11/99 | Leroux et al. | | | 03/27/97 |
| | A6 | 5,936,738 | 08/10/99 | Liebmann et al. | | | 08/03/98 |
| | A7 | 6,063,531 | 05/16/00 | Singh et al. | | | 10/06/98 |
| | A8 | 6,483,580 | 11/19/02 | Xu et al. | | | 03/06/98 |
| | A9 | 5,773,174 | 06/30/98 | Koizumi et al. | | | 07/09/97 |
| | A10 | 6,485,872 | 11/26/02 | Rosenthal et al. | | | 11/22/00 |
| | A11 | 6,304,999 | 10/16/01 | Toprac et al. | | | 10/23/00 |
| | A12 | 6,501,534 | 12/31/02 | Singh et al. | | | 04/30/01 |
| | A13 | 6,513,151 | 01/28/03 | Erhardt et al. | | | 02/26/01 |
| | A14 | 5,965,309 | 10/12/99 | Ausschnitt et al. | | | 10/28/97 |
| | A15 | 6,433,878 | 08/13/02 | Niu et al. | | | 01/29/01 |
| | A16 | 6,778,275 | 08/17/04 | Bowes | | | 02/20/02 |
| | A17 | 6,982,793 | 01/03/06 | Yang et al. | | | 04/04/02 |
| | A18 | 2004/0169861 | 09/02/04 | Meiher et al. | | | 12/05/03 |

Other Documents

| Examiner Initial | No. | Author, Title, Date, Place (e.g. Journal) of Publication |
|--|---|---|
|  ↓ ↓  | B1 | Junwei Bao, "A Lithography Focus Monitor Based on Scattering from 2D Gratings", downloaded May 22, 2002, http://buffy.eecs.berkeley.edu/IRO/Summary/99abstracts/junwei.1.html |
| | B2 | Junwei Bao., "A Spectral Scatterometry-Based Pilot Inspector", downloaded May 22, 2002, http://buffy.eecs.berkeley.edu/IRO/Summary/98abstracts/junwei.3.html |
| | B3 | Edgar et al., "Simultaneous Identification of Focus and Exposure Drifts in Control of Photolithography CD", downloaded May 22, 2002, Technical Program paper Detail - AICHe |
| | B4 | Ralph Foong, "Characterizing the Sensitivity of Spectral Scatterometry", Downloaded May 30, 2002, http://buffy.eecs.berkeley.edu/IRO/Summary/00abstracts/foong.1.html |
| Examiner |  | Date Considered 2/2/2004 |

| | | |
|--|---|---|
| Form 1449 (Modified) Information Disclosure Statement By Applicant (Use Several Sheets if Necessary) | Atty Docket No. KLA1P119 Applicant: Mieher et al. Filing Date January 17, 2004 | Application No.: 10/760,149 Group 2877 |
|--|---|---|

Other Documents

| Examiner Initial | No. | Author, Title, Date, Place (e.g. Journal) of Publication |
|--|---|---|
|  | B5 | Moers et al., "Application of the aberration ring test (ARTEMIS™) to Determine lens Quality and Predict its Lithographic Performance", Proceedings of SPIE Vol. 4346 (2001) |
|  | B6 | Xinhui Niu, "Spectral Scatterometry for CD Control", http://buffy.eecs.berkeley.edu/IRO/Summary/98abstracts/xniu.2.html |
|  | B7 | Niu et al., "Spectral Spectroscopic Scatterometry in DUV Lithography" |
|  | B8 | Joseph C. Pellegrini et al., "Emerging Trends in Photolithography Analysis and Control", New Vision Systems, Inc., Cambridge, MA. |
|  | B9 | Schoot et al., "Printing 130nm DRAM Isolation Pattern: Zernike Correlation and Tool Improvement", Proceedings of SPIE" vol. 4346 (2001) |
|  | B10 | Verhaegen et al., "CD Control for Two-Dimensional Features in Future Technology Nodes", Proceedings of SPIE, vol. 4346 (2001) |
|  | B11 | Yeung et al., "Inverse Obstacle Problem in Ellipsometric Scatterometry", Department of Manufacturing Engineering, Boston University. |
|  | B12 | "Metrology for the Future", European Semiconductor, August 2001 |
|  | B13 | "2.1 Some Fundamental Considerations", Downloaded May 22, 2002, www.iue.tuwien.ac.at/publications/PhD%20theses/Kirchauer/node.html |
|  | B14 | "3.2.1 Focus Effects and Process Window", Downloaded May 22, 2002, www.iue.tuwien.ac.at/publications/PhD%20theses/Kirchauer/node41.html |
|  | B15 | Mieher et al., "Spectroscopic CD Metrology for Sub-100nm Lithography Process Control", Proceedings of SPIE Vol. 4689 (2002). |
| Examiner  | Date Considered  | |

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.